

Amendments to the Claims

This listing of claims will replace all prior versions, and listings of claims in the application.

1. (currently amended) A cleaning device for process gases that generates clean process gas from contaminated process gas in ~~particularly of~~ a reflow soldering system comprising:

a plurality of cleaning chambers (15) containing a cleaning liquid for said process gas, each of said cleaning chambers ~~being adapted to be flown~~ allowing the contaminated process gas to flow therein through via a supply line (12) ~~for the contaminated process gas and allowing the cleaned process gas to flow therefrom~~ via a discharge line (13) ~~for the cleaned process gas, characterized in that~~

wherein the cleaning chambers are each formed by a plurality of modules of which such a great number is arranged to be flown through in parallel to allow for a predetermined that the required throughput of process gas is achieved, and ~~of which such a great number is arranged to be flown through in successive order that the required to allow for a predetermined~~ degree of purity is achieved for the process gas.

2. (currently amended) The cleaning device according to claim 1, ~~characterized in that~~ wherein the plurality of modules include modules having different operative principles of deposition that are connected one after ~~that~~ the other in series.

3. (currently amended) The device according to claim ~~1 or 2, characterized in that~~ wherein a flow path for the cleaning liquid extends through the series-connected modules in such a manner that the direction of flow of the cleaning liquid is opposite to the direction of flow of the process gas.

4. (currently amended) The cleaning device according to claim 1 ~~any one of the preceding claims, characterized in that~~ wherein the cleaning liquids with have different cleaning properties, such that respective ones of which are provided in respective ones of the plurality of cleaning chambers (15) of the Modules (31) which are arranged to be flown through in the successive order.

5. (currently amended) The cleaning device according to claim 1 ~~any one of the preceding claims, characterized in that~~ wherein at least a part of each of the plurality of cleaning chambers (15) contains a corresponding bath consisting of including the cleaning liquid (16), the supply line (12) terminating each time coupled below the liquid level of the bath in said bath.

6. (currently amended) The cleaning device according to claim 1 ~~any one of the preceding claims, characterized in that~~ wherein at least a part of each of the plurality of cleaning chambers (15) contains at least one deposition wall (25) on a the surface of which a film (28) of the cleaning liquid is positioned.

7. (currently amended) The cleaning device according to claim 6, ~~characterized in that~~ wherein the deposition walls (25) are arranged perpendicular or with a slope with respect to each other in the plurality of cleaning chambers (15) and the supply means for the cleaning liquid are arranged in an the area of on top of edges of the deposition walls deposition wall edges (26) obtained due to said arrangement, supply means (27) for the cleaning liquid are arranged that are directed thereto.

8. (currently amended) The cleaning device according to claim 1 ~~any one of the preceding claims, characterized in that~~ wherein at least one respective injection opening (29) for the cleaning liquid (16) is directed into at least part of each of the plurality of cleaning chambers (15).

9. (currently amended) The cleaning device according to claim 1 ~~any one of the preceding claims, characterized in that~~ wherein at least part of each of said plurality of cleaning chambers (15) ~~comprises~~ comprise a respective outlet (20) ~~which that~~ is connected to a clarifying device (18) for the cleaning liquid.